Synchrotron Radiation to study Atomic Layer Deposition

Tuesday, 14 June 2016

Talks 3 (09:00 - 13:05)

time	[id] title	presenter
09:00	[37] In-situ characterization during ALD	Prof. DETAVERNIER, Christophe
09:45	[31] The need for validation of ALD mechanisms predicted from first principles	Dr ELLIOTT, Simon
10:05	[18] Controlling the Ti Oxidation State in TiO2 – An In-Line XPS Study	Dr BRONNEBERG, Aafke
10:25	[10] In Situ Study of the Morphological Stability of ALD-Grown Pt Nanoparticles During Thermal Annealing	Dr SOLANO, Eduardo
10:45	Coffee break	
11:05	[24] SR X-ray diffraction and X-ray absorption fluorescence spectroscopy study of Er-doped HfO2 deposited by atomic layer deposition	Dr WIEMER, Claudia
11:25	[23] On the Oxidation State of MnOx – An In-Line XPS Study	Mr PLATE, Paul
11:45	[13] Quantitative and chemical characterization capabilities for atomic layer depositions using synchrotron-based reference-free X-ray spectrometry	Mr HOENICKE, Philipp
12:05	[32] XANES and XMCD of pure and Fe doped ZrO2 thin films grown by ALD	Dr LAMPERTI, Alessio
12:25	[26] Interfacial and surface effects during the growth of Sb2Te3/Sb2Se3 ternary films and multilayer structures studied by QCM in situ analysis.	Mr WIEGAND, Christoph
12:45	[20] In Situ High Temperature X-Ray Scattering Studies of some Atomic Layer Deposited Layers of Metals and Metal Oxides	Mr HEIKKILÄ, Mikko